



### Charged Hadron damage investigation of FBK and HPK Low Gain Avalanche Detectors

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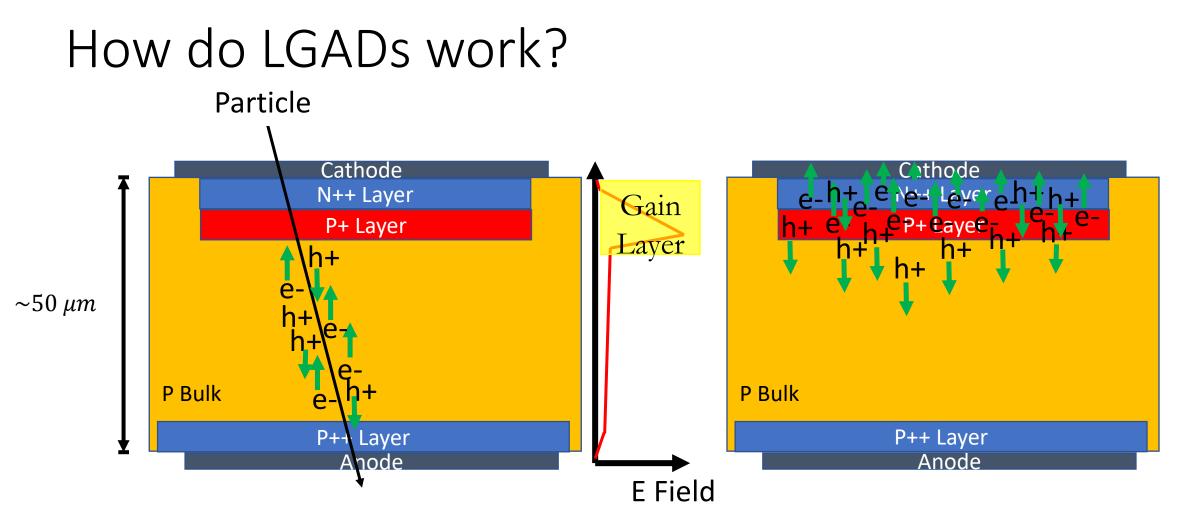
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**Jozef Stefan Institute** 

### Outline

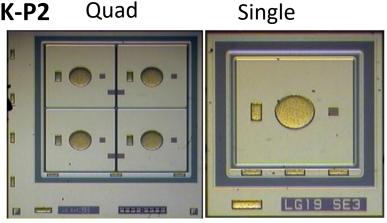
- The High Luminosity (HL) upgrade will increase the luminosity of the Large Hadron Collider (LHC) by a factor of ~10. Increased luminosity causes (1) increased fluence which degrades sensor performance and (2) increased readout complexity because of the pileup.
- Low Gain Avalanche Detectors (LGAD) will be primarily used for fast timing measurement in HL-LHC for the High-Granularity Timing Detector (HGTD) in ATLAS or the Endcap Timing Layer (ETL) of CMS. They are required to operate at a fluence up to 2.5x10<sup>15</sup> n<sub>eq</sub>/cm<sup>2</sup> (including a safety factor of 1.5).
- It is required that the HGTD be able to measure the times of arrival of minimumionizing particles (MIPs) with an average time resolution of approximately 35 ps per track at the beginning of the operation of the HL-LHC, 70 ps at the end of the operation of the HL-LHC.
- Initial characterization measurements of unirradiated/irradiated LGADs manufactured by Hamamatsu Photonics (HPK) and Fondazione Bruno Kessler (FBK) are underway at UNM.





In silicon sensors, charge multiplication happens when charge carriers drift in a region with an electric field (E) greater than about 300 kV/cm. The additional P+ (or gain) layer, when depleted, locally generates an electric field high enough to activate the avalanche process.

#### Our study includes LGADs manufactured by Hamamatsu Photonics (HPK) and Fondazione Bruno Kessler (FBK). **HPK-P2** Quad



- $n ++ (electrode) 1.3 \times 1.3 \text{ mm}^2$
- $p + (gain layer) 2.2 to 2.5 \mu m thick$
- p (bulk)
- p ++ (backside)

50 µm thick active layer

200 µm total thickness

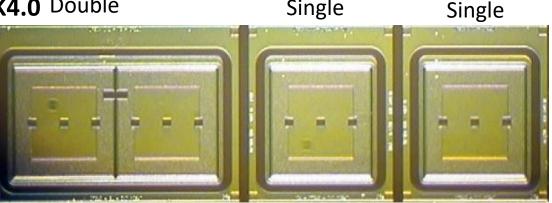
single guard ring

variations with and without under-bump metallization (UBM)

epitaxial Si grown on Czochralski substrate

FBK4.0 Double

Single



n ++ (electrode) – 1.3 x 1.3 mm<sup>2</sup> Quad

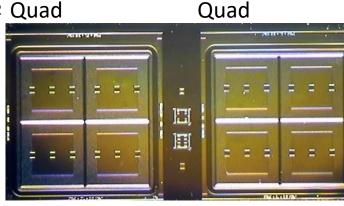
- $p + (gain layer): 0.7-2\mu m$  thick
- (bulk) р

p ++ (backside)

55 µm thick active layer multiple guard rings

The depth of the gain implant

varies in different samples.

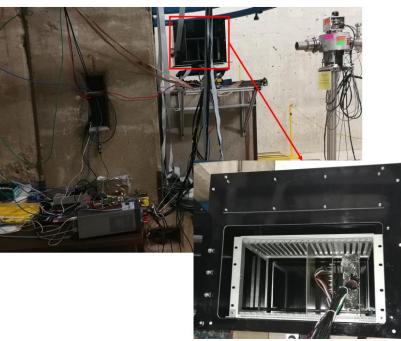


In FBK sensors, carbon co-implantation in the gain layer is used to improve radiation resistance. The carbon dose varies in different. samples.

### LANSCE/FNAL Proton Irradiation

In 2022, we did two irradiation runs. One at Fermi National Accelerator Laboratory (FNAL) in May, and the other one at Los Alamos Neutron Science Center (LANSCE) in July. Normally at LANSCE we get 800 MeV protons, but in July 2022 run, we irradiated the FBK samples with 500 MeV protons.



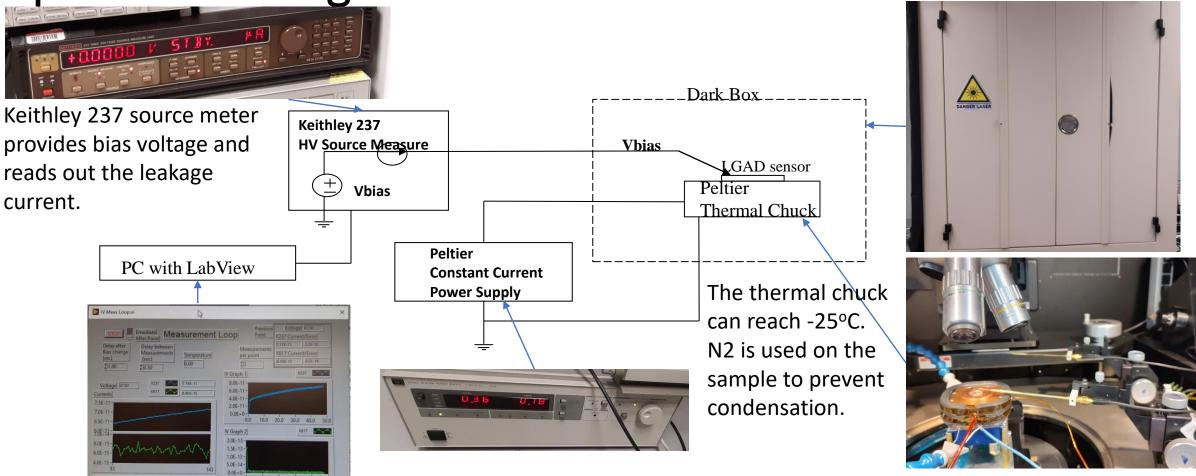


At the FNAL facility, we irradiated HPK samples with 400 MeV protons in May.

Irradiated samples are stored in -25C freezer.



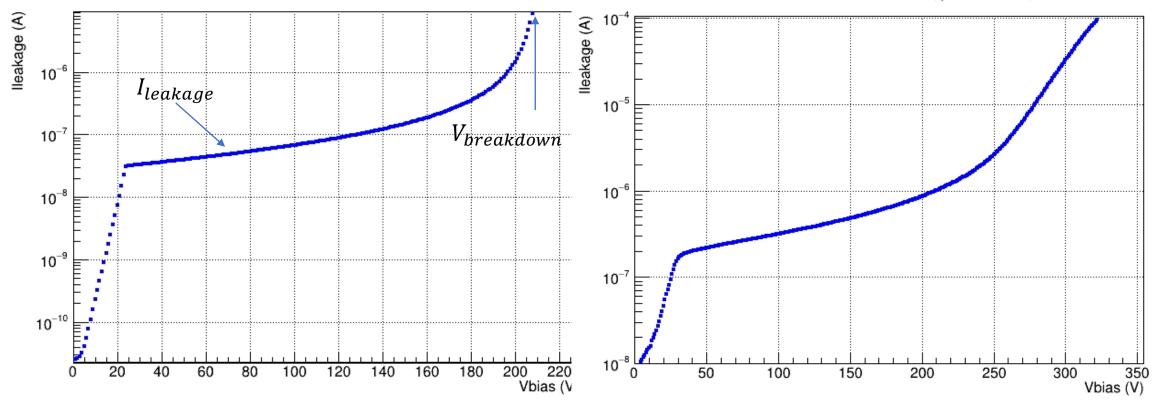
# Current vs. Voltage (IV) measurements are used to measure leakage currents, breakdown voltages, and determine the operational ranges.



## Irradiation increases leakage currents and breakdown voltages of LGADS

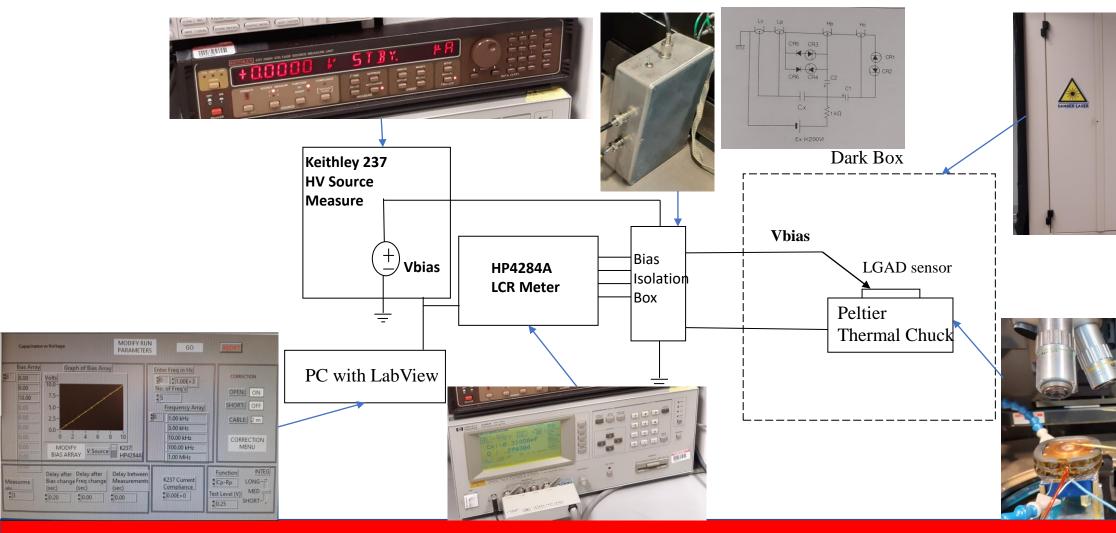
IV of W9 D1 1x3(1) R, unirradiated, at 20C

IV of W9 D1 1x3(1) R, irradiated (2x10<sup>14</sup>n<sub>eq</sub>/cm<sup>2</sup> 500MeV p), at -25C



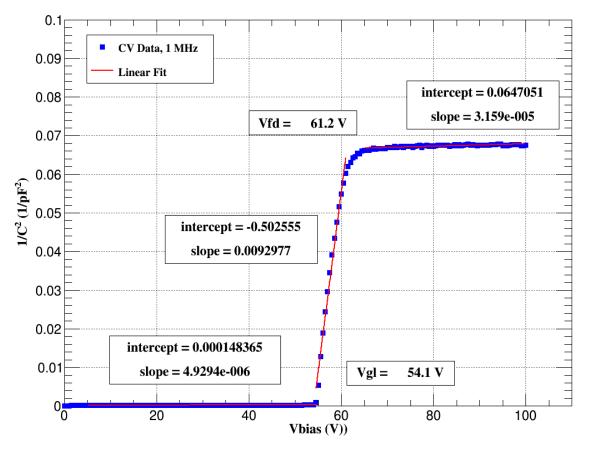


## Capacitance vs. Voltage (CV) Measurements are used to measure the depletion voltage

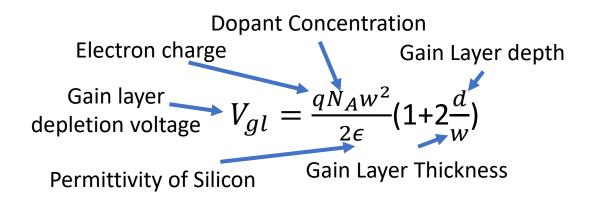


## CV Measurements are used to extract the gain layer depletion voltage $V_{gl}$ and full depletion voltage $V_{fd}$

W25 Pre-Irradiated 1E14 A

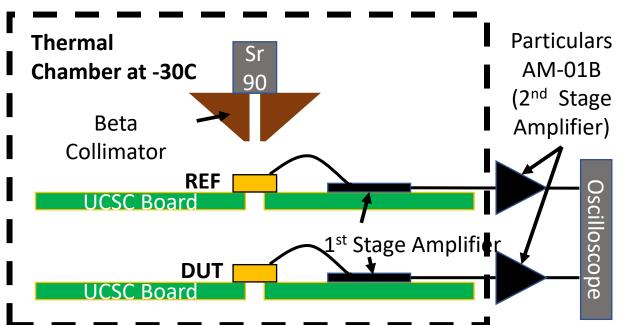


The depletion voltage of the gain layer depends on the dopant concentration, which is impacted by radiation fluence

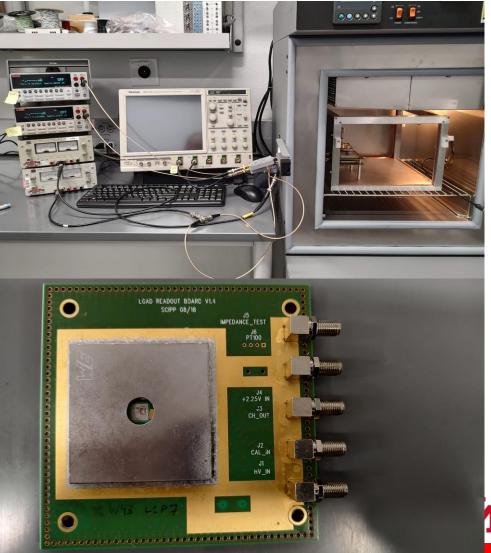


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## β-source setup is used to study the timing performance of LGADs



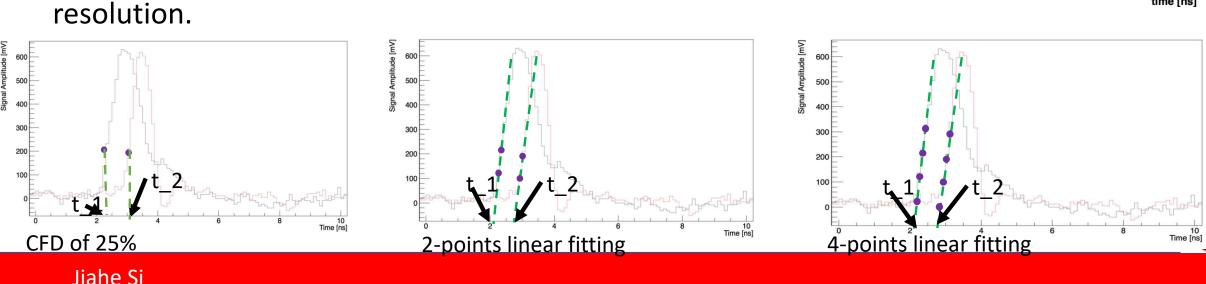
- LGADs are mounted on the single channel readout board developed by UCSC.
- Tektronix DPO 7254 Oscilloscope with 2.5GHz bandwidth, 40GS/s sampling rate is used.
- Shortest cables are used to connect to the oscilloscope for best signal-to-noise performance.
- Time resolution requirement: 35 ps (start) and 70 ps (end of life).
  Jiahe Si

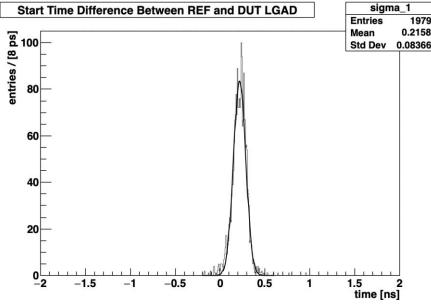


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### 3 methods were used to calculate the resolution

- Only signals triggering both REF and DUT channels are collected.
- The resolution is calculated from the temporal deviation of ~2000 events.
- Constant Fraction Discriminator (CFD) method of 25%, 2-point linear fitting, and 4-point linear fitting were used, the differences are within a few percent.
- Equation  $\sigma_{tot}^2 = \sigma_{REF}^2 + \sigma_{DUT}^2$  is used to calculate the resolution.



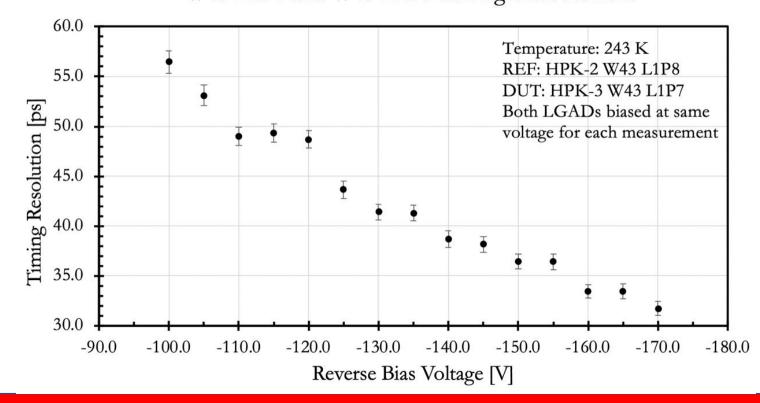


### Two identical HPK sensors (unirradiated) are

### used as the references for timing measurements

When measuring the timing of two identical sensors,  $\sigma_{REF} = \sigma_{DUT}$  so a single measurement will give you the temporal resolution of both sensors.

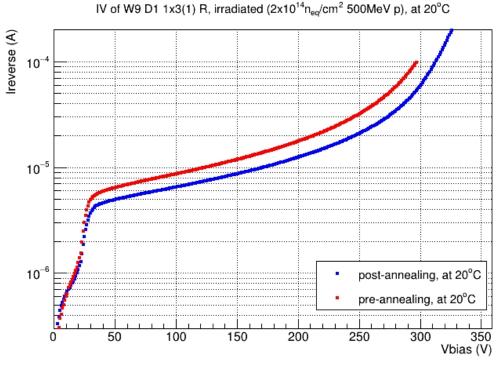
Either of the unirradiated sensors can be used as the reference for the timing measurements for<br/>the irradiated sensors.W43-L1P7 and W43-L1P8 Timing Measurement



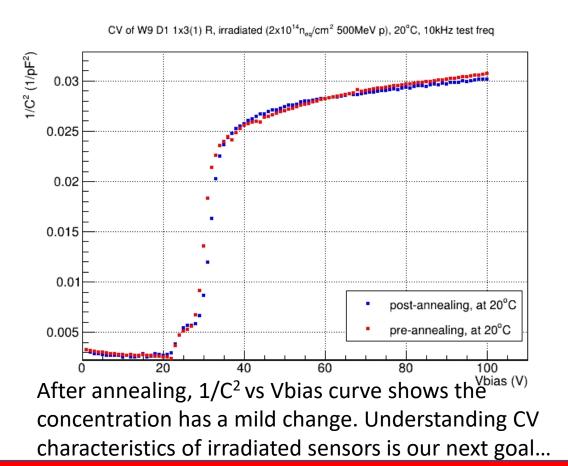


## Study of the effect of high temperature annealing upon LGAD capacitance and current

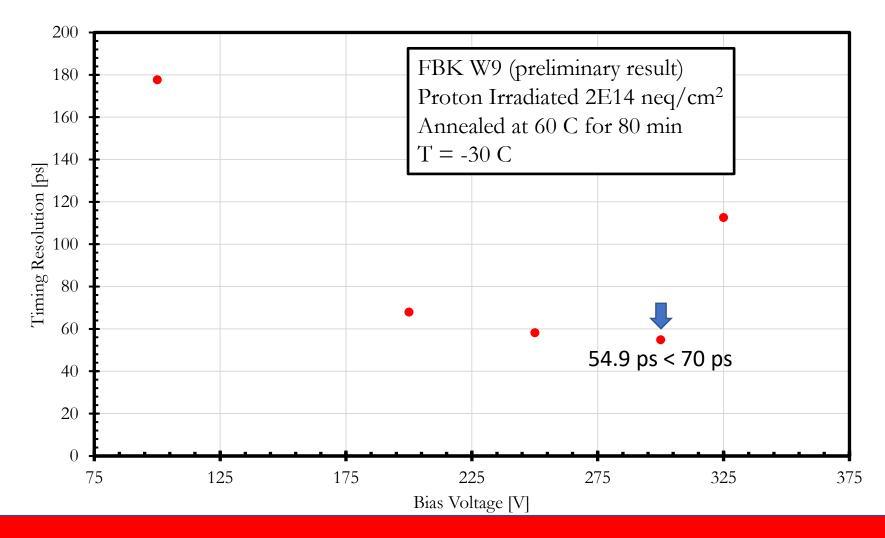
To match the LGAD community's standard procedure, irradiated samples were annealed at 60°C for 80 minutes. However, pre-annealing measurements were also performed.



After annealing, leakage current reduced by ~1/3, Breakdown voltage increased ~20V.



## Preliminary timing resolution measurement is ongoing...



### Summary

- We have set up the instruments for IV, CV, and timing measurement.
- Two irradiation runs were performed at FNAL and LANSCE in 2022.
- Pre-irradiation measurements were performed.
- Working on post-irradiation measurements (just started).
- With the LGADs irradiated at different fluences, one of our goals is to estimate acceptor removal coefficients using  $V_{gl} = \frac{qN_Aw^2}{2\epsilon}(1+2\frac{d}{w})$
- There are still many samples to measure and study...



### Thank You!



### Backup Slides



From Technical Design Report: A High-Granularity Timing Detector for the ATLAS Phase-II Upgrade p88 ATLAS-TDR-031.pdf

Technology	Silicon Low Gain Avalanche Detector (LGAD)
Time resolution	pprox 35 ps (start); $pprox$ 70 ps (end of lifetime)
Time resolution uniformity	No requirement
Min. gain	20 (start); 8 (end of lifetime)
Min. charge	4 fC
Min. hit efficiency	95%
Granularity	$1.3\mathrm{mm}  imes 1.3\mathrm{mm}$
Max. inter-pad gap	100 μm
Max. physical thickness	300 µm
Active thickness	50 μm
Active size	$39\mathrm{mm} imes19.5\mathrm{mm}$ ( $30 imes15$ pads)
Max. inactive edge	500 μm
Radiation tolerance	$2.5 \times 10^{15} \mathrm{n_{eq}} \mathrm{cm}^{-2}$ , 1.5 MGy
Max. operation temperature on-sensor	−30 °C
Max. leakage current per pad	5μA
Max. bias voltage	800 V
Max. power density	$100 \mathrm{mW/cm^2}$

Table 5.1: Sensor parameters and requirements.

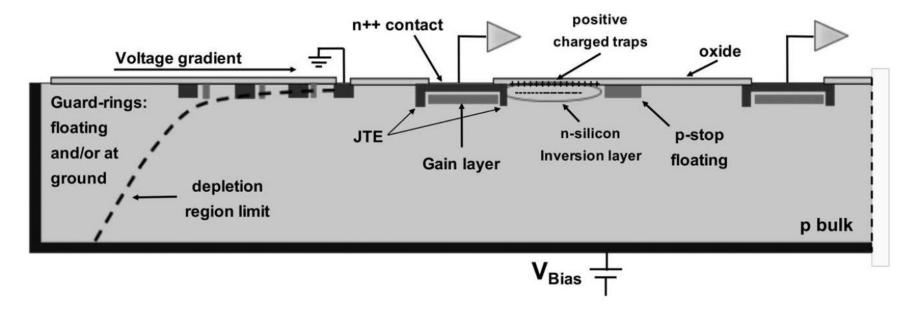
From Technical Design Report: A High-Granularity Timing Detector for the ATLAS Phase-II Upgrade p110 ATLAS-TDR-031.pdf

#### Annealing

Most of the measurements with irradiated sensors were done after annealing for 80 min at 60 °C, which roughly simulates the operational conditions in one year of LHC operation since higher temperature accelerates the annealing (the Arrhenius factor between 60 °C and -30 °C is more than 1 × 10<sup>6</sup>, 80 min simulates hundreds of years at -30 °C, and tens of days at room temperature).



The actual design includes p-stops to limit inter-pad current, guard rings, and junction termination extensions which mitigate breakdown voltage, and other features.



**Figure 2.21** Cross cut of a multi-pads UFSD (not to scale) with a schematic view of the building blocks of the device. From the device physical edge: guard-rings, pad with JTEs, inter-pad region with *p*-stop.

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Using the information provided by the C(V) measurements, it is possible to:

1. extract the gain layer implant profile (amplitude, width, depth) by computing the active doping concentration  $N_A(d)$  as a function of depth d. This is obtained by first calculating d from the value of C with

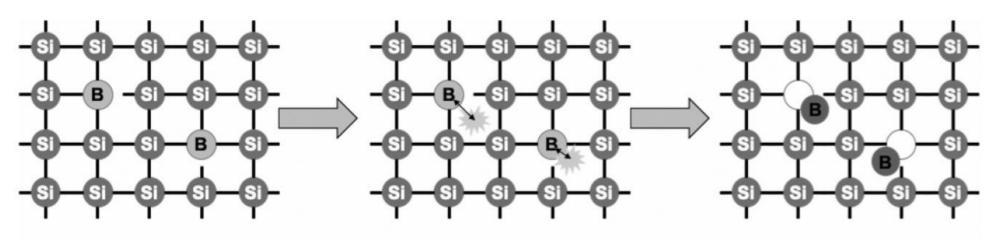
$$d = \frac{\varepsilon_{\rm Si}A}{C} \tag{4.4}$$

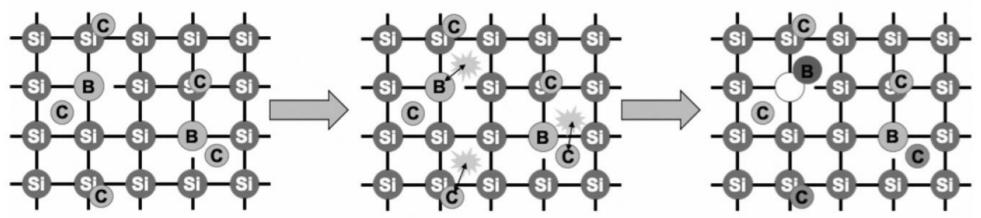
and then the doping density at that depth *d* with:

$$N_{\rm A} = \frac{2}{\varepsilon_{\rm Si} q A^2 \frac{\partial 1/C^2}{\partial V}},$$

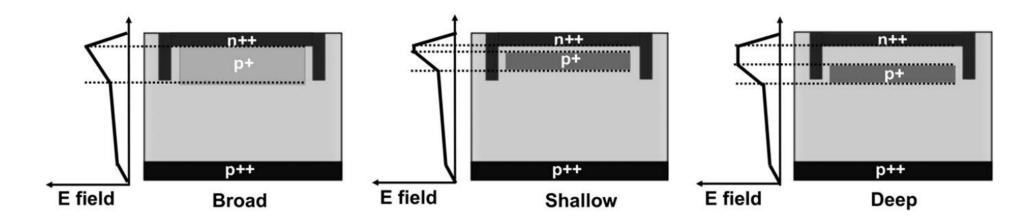
(4.5)

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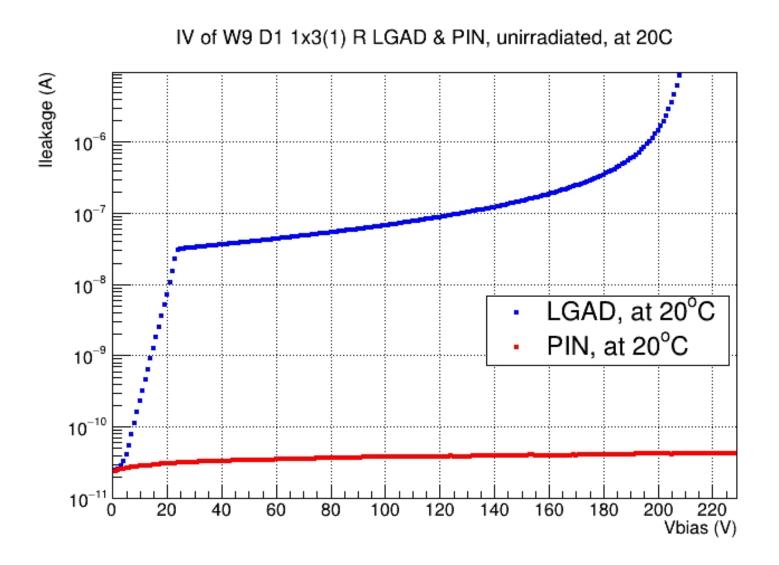


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**Figure 2.3** Schematic cross cut of a UFSD with broad (*left*), shallow (*middle*), and deep (*right*) gain implants and their respective electric field profiles.





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